ABSTRACT

An abatement system and method for the abatement of contaminants of effluent gases produced during the manufacture of semiconductor devices. A burn/wet scrubber is provided at the device fabrication site where toxic effluent gases are produced. The burn/wet scrubber oxidizes and condenses toxic compounds.

Wastewater used to condense oxidized toxic gases is treated locally in an ion exchange filter. The treated wastewater is then directed to a centralized wastewater treatment facility.